IN THE SPECIFICATION

Please replace the paragraph at page 2, prenumbered line 17, through page 3, prenumbered line 7, with the following rewritten paragraph:

As shown in Fig. 5, an optical exposure stage 210 is provided with recesses 212, which are used to set a TFT array substrate on the exposure stage 210 or to detach it from the stage 210, and plates 214. Although the recesses 212 do not reflect incident light, the plates 214 reflect it as shown by dotted lines and arrows. Thus, portions of an insulation film 128 corresponding to the recesses 212 receive incident light passing through a photomask 208. The other portions of the insulation film 128 corresponding to the plates 214, however, receive not only incident light passing through the photomask 208 but also reflecting light from the plates 214. Since pattern dimensions depend on ~~receiving~~ a received quantity of light, patterns of the portions positioned above the recesses 212 are small in width but those of the portions positioned above the plates 214 are wide in width though not shown in different widths in Fig. 5. Such ~~pattern~~ different widths ~~between them~~ in the patterns cause visibly uneven brightness of images displayed by an LCD device.

Please replace the paragraph at page 3, prenumbered lines 14-17, with the following rewritten paragraph:

It is another object of the present invention to provide an LCD device with improvement of such visibly uneven brightness caused by ~~pattern~~ width ~~difference~~ differences in patterns resulting from ~~receiving~~ a received quantity of light reflecting from an optical exposure stage.

Please replace the paragraph at page 9, prenumbered line 9, to page 10, prenumbered line 4, with the following rewritten paragraph:

Further, there are two different length optical paths by way of the liquid crystal layer 180 through which light passes in response to transparent and reflective display modes of the LCD device shown in Fig. 1, respectively. Namely, when the LCD device carries out the transparent display mode, light from a rear light source 190 passes through the liquid crystal layer 180 once. However, when it carries out the reflective display mode, incident light from color photoresist film 144 passes through the liquid crystal layer 180 and light reflecting from the reflective electrode 132 passes through the liquid crystal layer 180 again. Where the height of the reflective electrode 132 is the same as that of the transparent electrode 130, the optical length of the reflecting light is much longer than that of the light passing through. Thus, in order to obtain optimal optical characteristics in both transparent and reflective display modes, the cell gaps between the transparent electrode 130 and the electrode 146 and that between the reflective electrode 132 and the electrode 146 are necessarily designed to be optimum. The former is bigger than the latter as shown in Fig. 1 to adjust the optical lengths to be optimum. For that purpose, optical exposure is carried out only for the regions in the substrate on which the transparent electrodes are formed and, then, the substrate is subjected to development and post baking processes.[[.]]

Please replace the paragraph at page 10, prenumbered lines 17-24, with the following rewritten paragraph:

As shown in Fig. 3C, the radiating light passes through the ~~recess~~ hole 212 of an optical exposure stage 210 and travels to the other side of the exposure stage 210. The reflecting light from the plates 214, on the other hand, travels in the glass plate 122 again but does not reach the insulation film 128 because the light shielding films 126 stop it. Thus, the

portions of the insulation film 128 positioned above both the ~~recess~~ hole 212 and the plates 214 receive substantially the same quantity of light.

Please replace the paragraph at page 11, prenumbered lines 13-19, with the following rewritten paragraph:

Since, as described above with respect to the first embodiment, the receiving quantity of light is substantially equal for both portions of the insulation film 128 positioned above the ~~recesses~~ holes 212 and the plates 214, neither the patterns positioned above the ~~recesses~~ holes 212 become narrow in width nor those above the plates 214 become wide in width. Its structure does not bring about an uneven display.

Please replace the paragraph at page 13, prenumbered lines 4-23, with the following rewritten paragraph:

A photosensitive organic insulation film 406 is then coated on the glass plate 402 on which the thin film transistors, etc. are formed (Fig. 4B). The glass plate 402 provided with the reflective and insulation films 404 and 406 on its dual surfaces, respectively, is loaded on an optical exposure stage 410. The exposure stage 410 is provided with ~~recesses~~ holes 412 used to set the glass plate 402 on the exposure stage 410 or to detach it from the stage 410. Light from a light source 422 is radiated only through transparent portions with the photomask 420. The radiated light does not pass through the reflective film 404 but reflects from it. Such reflecting light passes through the glass plate 402 and the insulation film 406 again and returns to the photomask 420. The quantity of the light passing through, and returning to, the insulation film 406 is substantially the same whether the transparent regions are positioned above the ~~recesses~~ holes or not. Dimensions or shapes of the uneven portions of the insulation film 406 formed after the exposure and development treatments are

substantially the same whether the transparent regions are positioned above the ~~recesses~~ holes or not. Thus, an uneven display is not visually recognized on the LCD device.

Please replace the paragraph at page 14, prenumbered line 22 to page 15, prenumbered line 4, with the following rewritten paragraph:

With the structure described above, the total receiving quantity of light at the portions positioned above the ~~recesses~~ holes 412 of the exposure stage 410 is substantially the same as that at the portions positioned above absence of the ~~recesses~~ holes 412 of the exposure stage 410. Thus, pattern sizes formed on the insulation film 406 are not different whether such pattern is positioned above the ~~recesses~~ holes 412 of the exposure stage 410 or not. An uneven display has not been visually recognized in the second embodiment LCD device, either.